



FOR IMMEDIATE RELEASE

HORIBA Semiconductor Introduces EV 2.0 End Point Monitor

SUNNYVALE, CA July 10th, 2018 – HORIBA Semiconductor, global leader in Process Metrology and Control Components announces the introduction of the EV 2.0 End Point Monitor.

EV 2.0 is a configurable, high performance spectrograph that can be customized for a variety of OEM/End-user applications including but not limited to ALD/ALE, dry etch, deposition and plasma cleaning and deposition processes. The spectrograph can be used for enhanced process control, stability / drift monitoring and endpoint detection.

With its proprietary high resolution holographic spectrograph equipped with a 2048x16 pixels Back-Thinned CCD and a fast 16 bits acquisition electronics, the EV 2.0 is capable of acquiring plasma light emission with optimised signal to noise ratio from 200 to 1050 nm (STD model). Exposure time varies from 20 ms to 2.5s to observe weak or intense plasmas.

“The EV 2.0 is a successor to HORIBA’s EV 140 and includes a host of new features and capabilities. In particular the new spectrograph includes easy-to-use software that not only provides continuous process monitoring but also can be used to create process recipes. This extension of the EV 140 series shows how HORIBA continues to invest in research and development that drives solutions to process problems” said Kevin Yoo, Applications Engineering Manager at HORIBA Semiconductor.

HORIBA technologies for process monitoring are used globally in applications that demand the highest performance. The EV 2.0 represents an innovative development that caters to specific customers’ process performance needs. The development of the supporting software indicates HORIBA’s commitment to enhanced packaging of our solutions in a way that allows our customers to easily install, integrate and operate them. To see the spectrograph in real life, visit our booth number 517 at Semicon 2018 in San Francisco.

HORIBA Semiconductor, part of HORIBA INSTRUMENTS, INC., headquartered in the United States, provides an extensive array of instruments and solutions for applications across a broad range of Semiconductor processes. HORIBA Semiconductor is a world leader in the measurement and control of critical process chemistries. Our instruments are found in equipment and facilities worldwide and HORIBA is a recognized technology leader in the Semiconductor industry.

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EV 2.0: HORIBA's EV 2.0 provides accurate and repeatable endpoint detection. The system is configurable and uses a proprietary high resolution holographic spectrograph that provides a new level of performance ideal for ALD/ALE, dry etch, plasma cleaning, and deposition processes. Come and see HORIBA's latest process endpoint detection innovation at Booth 517.

[Click here to learn more.](#)

HORIBA

OES Endpoint
Monitor for
critical processes



Optical Emission
Spectroscopy
Endpoint Detector
EV2.0

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